

Title (en)

Platen with web release apparatus

Title (de)

Platte mit Polierkissen Hebevorrichtung

Title (fr)

Plateau avec dispositif de sustentation du tampon de polissage

Publication

EP 1088622 A2 20010404 (EN)

Application

EP 00121213 A 20000929

Priority

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Abstract (en)

Generally, a method and apparatus for releasing polishing material in a polishing system. In one embodiment, the apparatus includes a platen having one or more nozzles coupled thereto. The platen has a support surface adapted to support the polishing material. The nozzles are adapted to flow a fluid therethrough that places the polishing material in a spaced-apart relation to the platen. In another embodiment, the one or more nozzles further include a centerline that forms an acute angle with the support surface. In one embodiment, the method includes the steps of supporting at least a portion of the polishing material on the platen, supplying a fluid between the polishing material, and lifting the polishing material to a spaced-apart relation to the platen. <IMAGE>

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